

Analog IC Design – Cadence Tools

LPF Simulation and MOSFET Characteristics

Lab 01

Part 2: MOSFET Characteristics

1. ID vs VGS

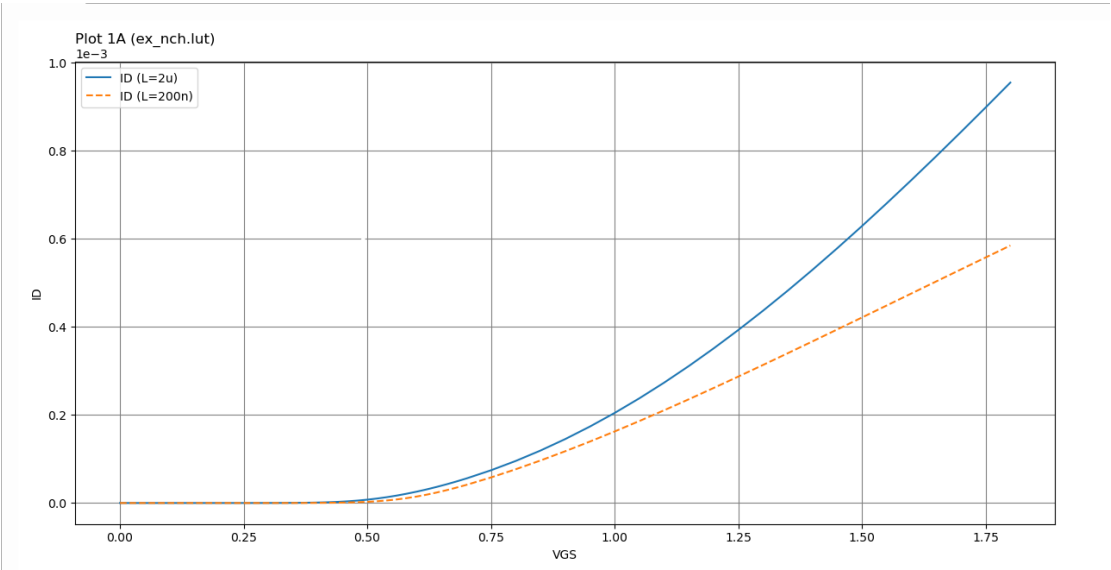


Figure 1 N_MOS ADT

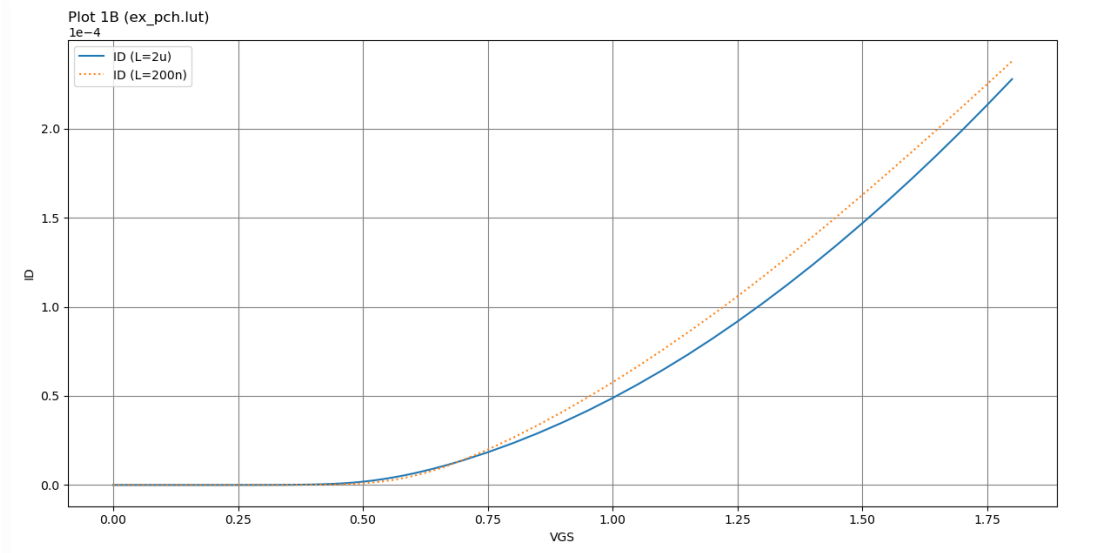


Figure 2 P_MOS ADT

the differences between short-channel and long-channel results.

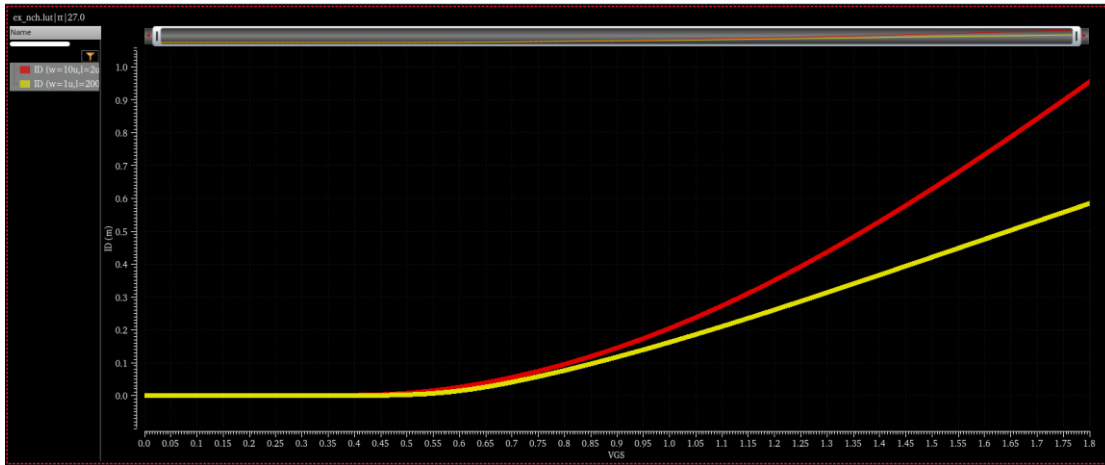


Figure 3 Id vs VGS for NMOS (Sizing Assistant)

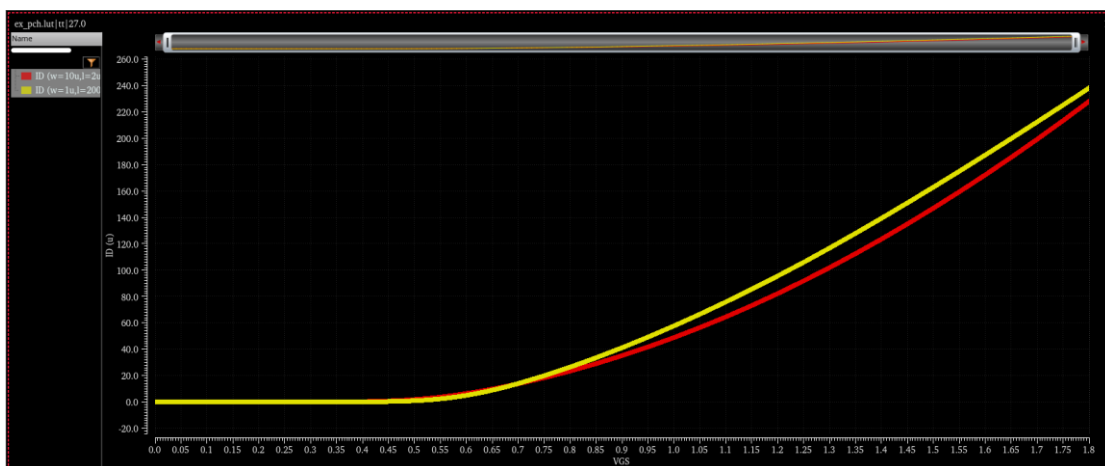


Figure 4 Id vs VGS for PMOS (Sizing Assistant)

Short Channel vs Long Channel

The long channel device has a higher current than the short channel, this is different from what we deduce from the square law that the two currents are equal if the value of the VGS is equal and the characteristics are constant. This means that the square law is not reliable in this case because of the effect of the channel length modulation, which comes from the change of the electric field, which is related to the length when the voltage is constant.

The relation for the Short Channel device is more linear than the Long Channel, because of the Velocity-Saturation, as the electrical field along the channel reaches a critical value the velocity of carriers tends to saturate and the mobility degrades, which make the curve more linear.

But the long channel device hasn't Velocity-Saturation so that it follows the square law and the curve is more quadratic not linear.

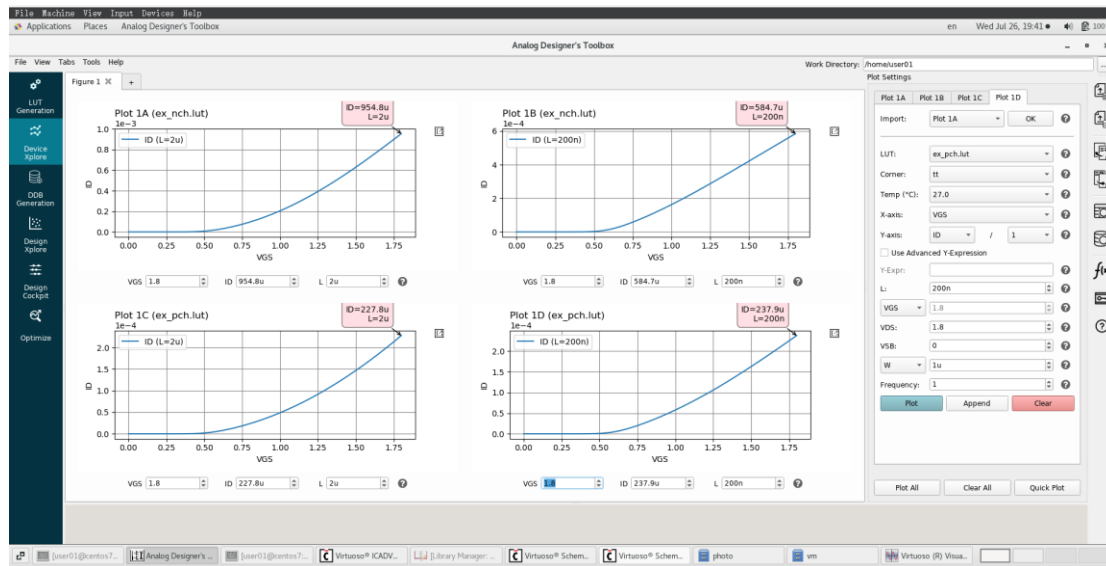
The differences between NMOS and PMOS.

NMOS has a higher current than PMOS, Because NMOS uses electrons while PMOS devices use holes, and the mobility of electrons is more than that of holes, This means that electrons can move more easily and quickly through the channel, resulting in higher current flow in NMOS devices.

The ratio between NMOS and PMOS currents at $V_{GS} = V_{DD}$ is

$$\text{For Short channel} = \frac{I_{Dn}}{I_{Dp}} = \frac{584.7\mu}{237.9\mu} = \frac{\mu_n}{\mu_p} = 2.4577535939$$

$$\text{For Long channel} = \frac{I_{Dn}}{I_{Dp}} = \frac{954.8\text{u}}{227.8\text{u}} = \frac{\mu_n}{\mu_p} = 4.19139596137$$



NMOS is more affected by short-channel effects, as it changes by larger factor than PMOS.

2.gm vs VGS

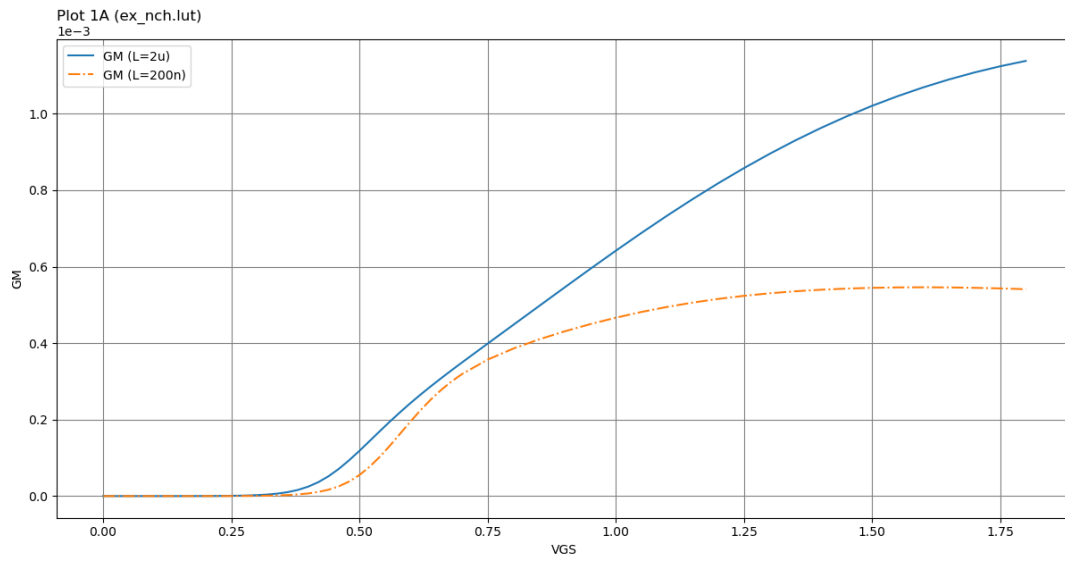


Figure 5 gm vs VGS N_MOS ADT

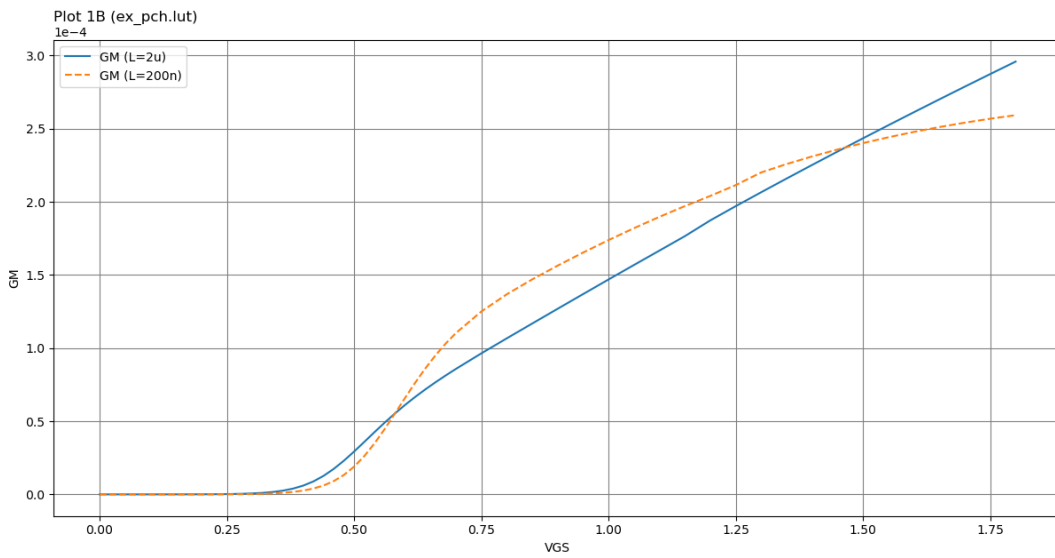


Figure 6 gm vs VGS P_MOS ADT

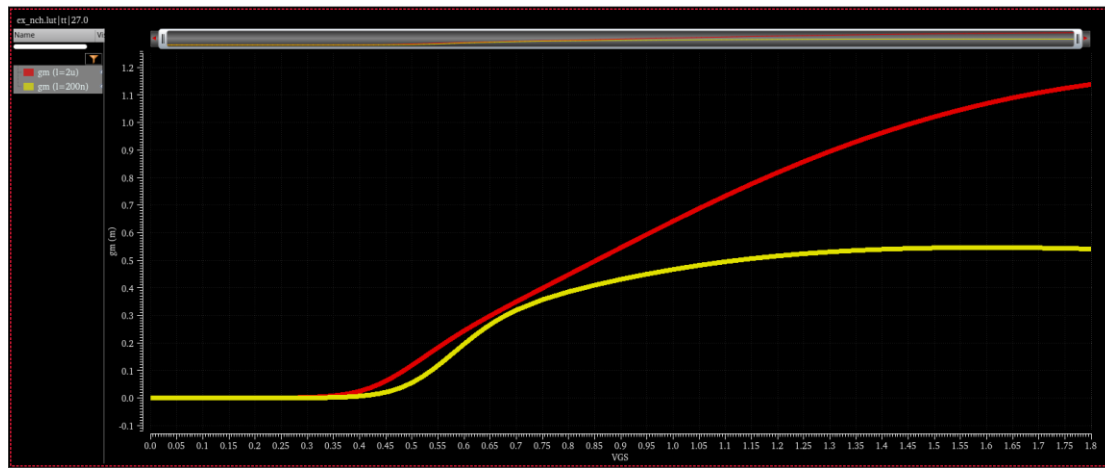


Figure 7 gm vs VGS N_MOS (Sizing Assistant)

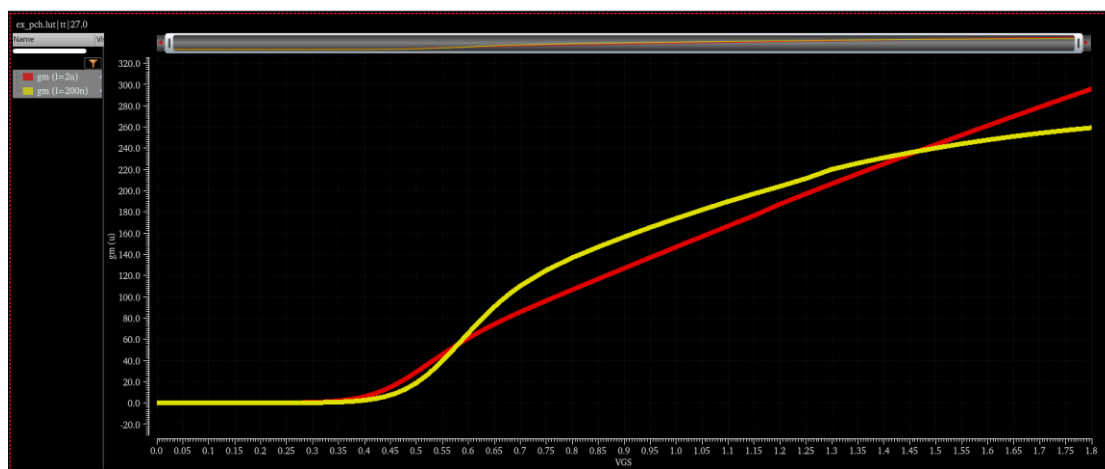


Figure 8 gm vs VGS P_MOS (Sizing Assistant)

the differences between short-channel and long-channel results:

gm saturates in Short channel & Long channel, as $g_m = \frac{\partial I_D}{\partial V_{GS}}$ and the result of this relation is different due to the channel length effect.

In the long channel device gm increases linearly because of the square law, and it's following the equation:

$$g_m = \frac{\partial I_D}{\partial V_{GS}} = K_n * (V_{GS} - V_{TH})$$

But for the long channel device it is not linear because the Velocity-Saturation which have an average due to phonon scattering which mean that its derivative isn't a linear relation.

3.ID vs VDS

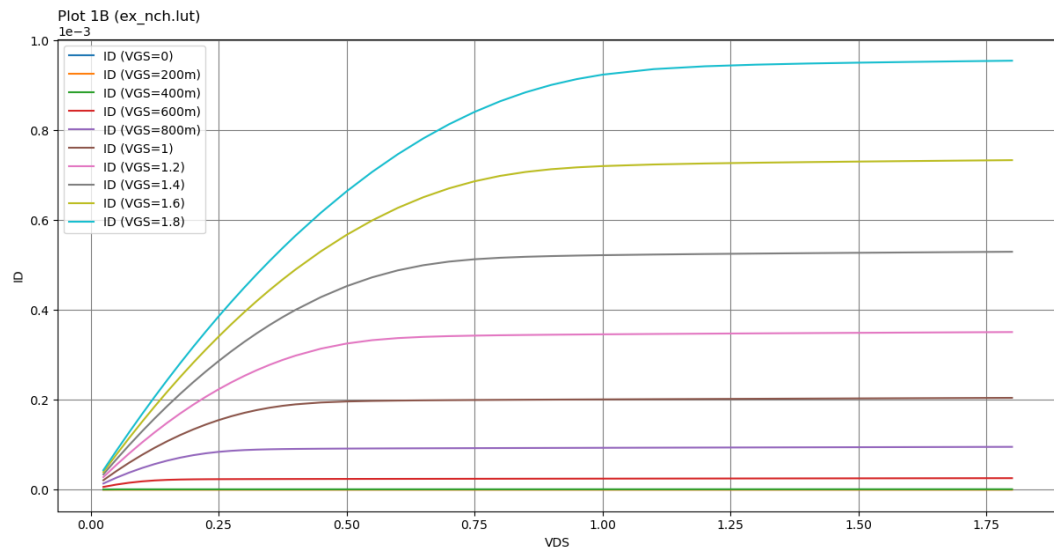


Figure 9 I_D vs V_{DS} N_MOS long channel ADT

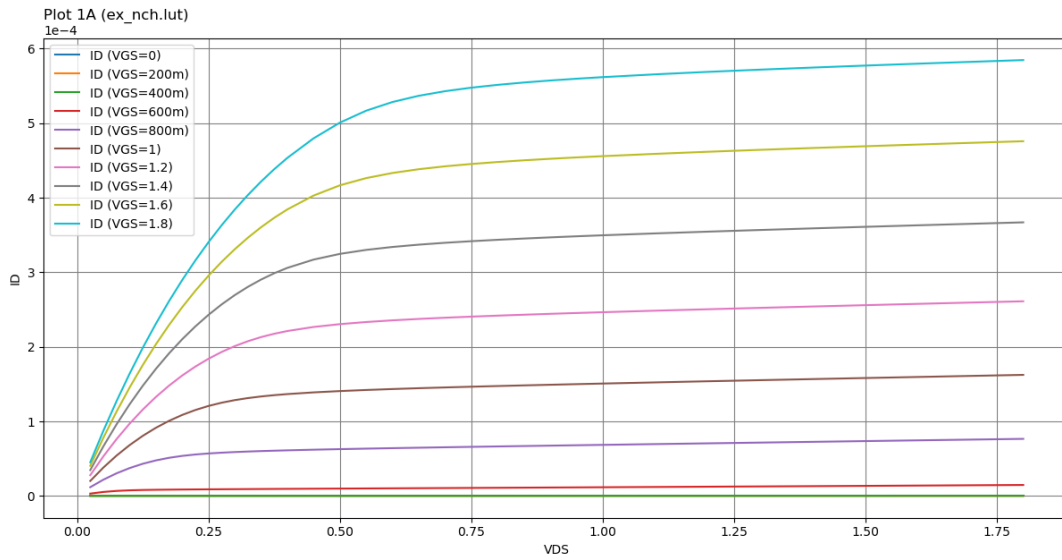


Figure 10 I_D vs V_{DS} N_MOS short channel ADT

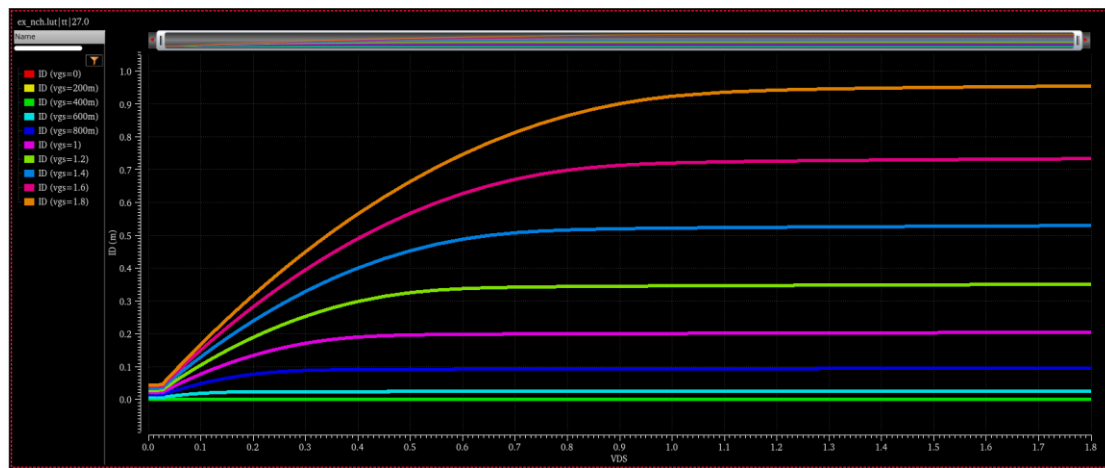


Figure 11 Id vs VDS N_MOS long channel ADT

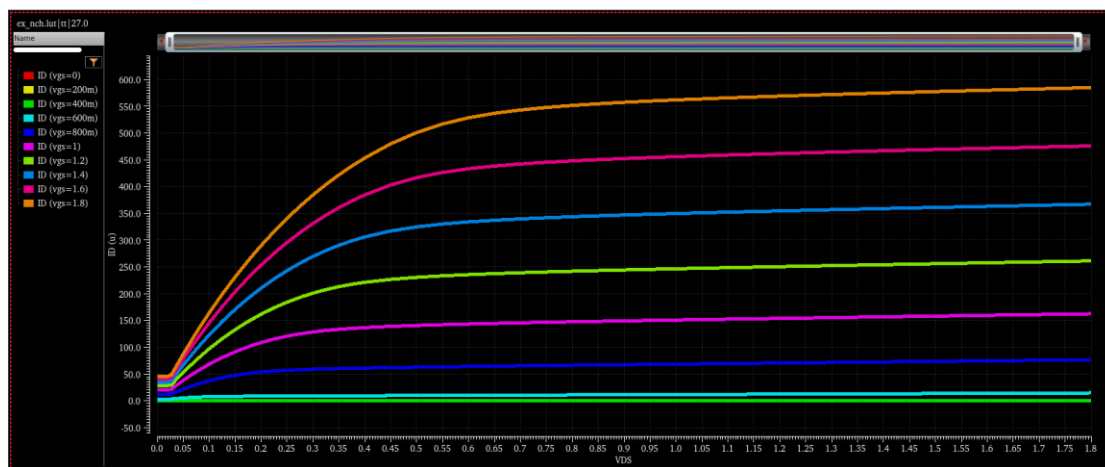


Figure 12 Id vs VDS N_MOS short channel ADT

The differences between short channel and long channel results.

Long channel has higher current, because the effect of the Velocity-Saturation in the short channel device which come because the phonon scattering.

Short channel has higher slope in the saturation region, because the channel length modulation effect as a resistance and the length of the channel is inverse proportional with the value of the resistance, and Short channel has higher resistance so it has higher slope in the saturation region.

[Optional] g_m and r_o in Triode and Saturation

- 1) Plot g_m and r_o vs V_{DS} for NMOS device. Use $W = 10\mu m$ and $L = 2\mu m$, $V_{DS} = 0: 10m: V_{DD}$, and $V_{GS} \approx V_{TH} + 0.5V$.

$$V_{TH} \approx 0.4$$

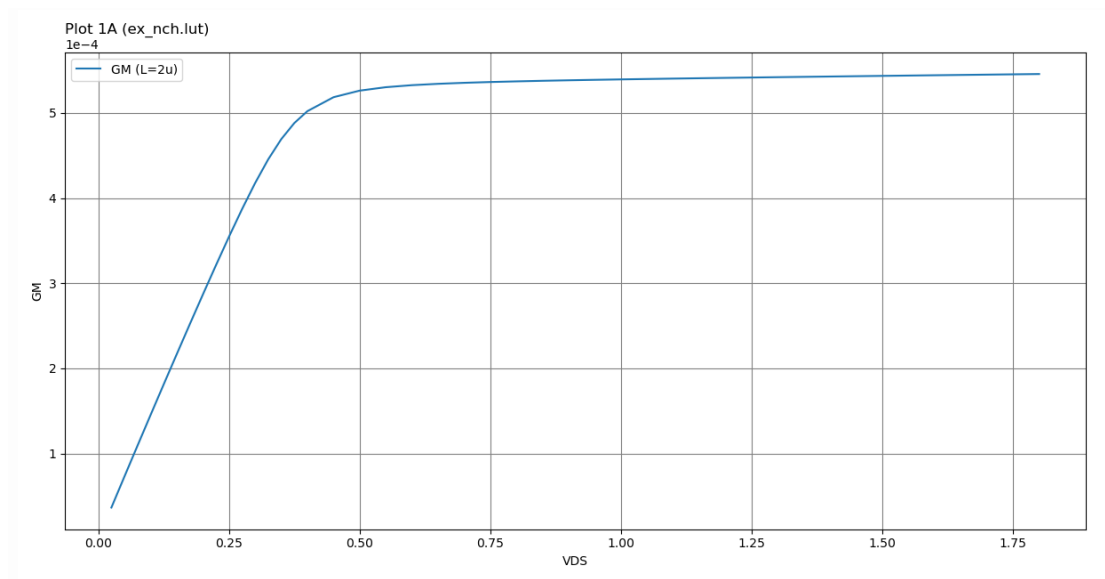


Figure 13 g_m vs V_{DS} N_MOS ADT

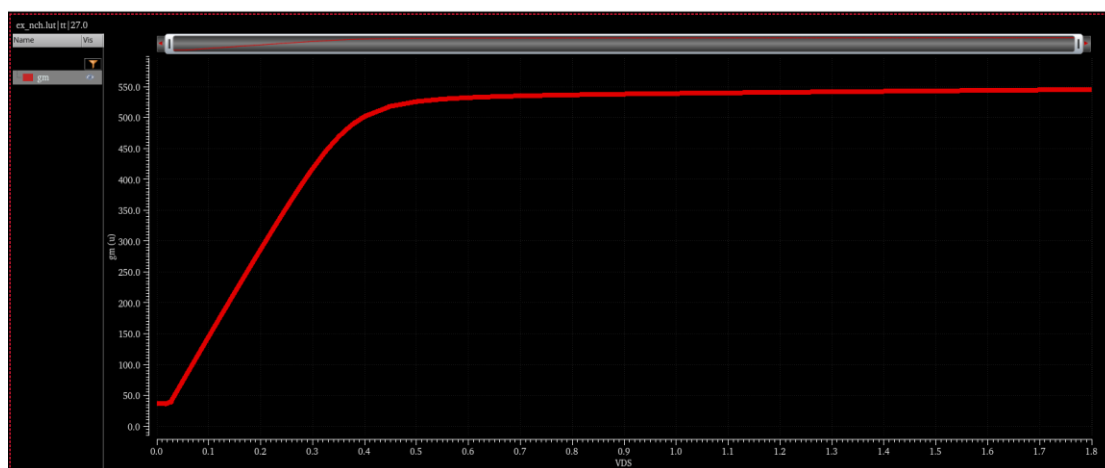


Figure 13 g_m vs V_{DS} N_MOS (Sizing Assistant)

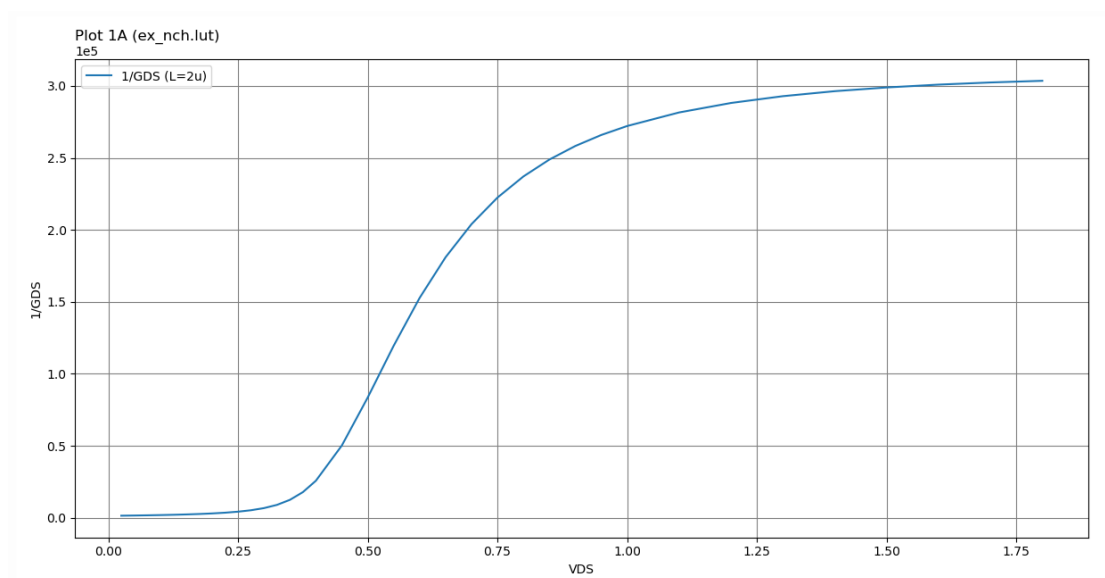


Figure 13 ro vs VDS N_MOS ADT

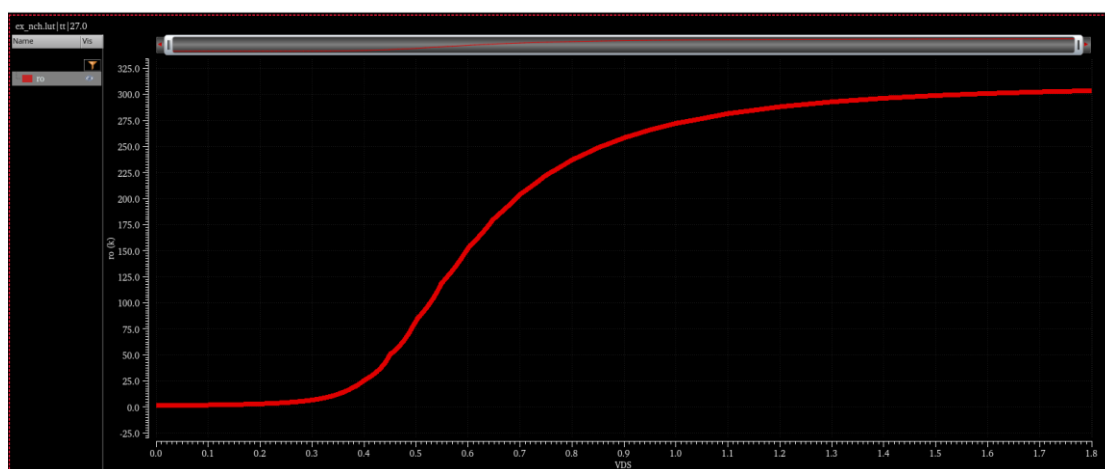


Figure 13 ro vs VDS N_MOS (Sizing Assistant)

2) Comment on the variation of gm vs V_{DS} .

We can describe the behaviour of gm vs V_{DS} in 3 regions :

Triode Region when ($V_{DS} < V_{ov}$) :

In this region, the NMOS operates as a voltage-controlled resistor if as ($K_n V_{ov} \gg \frac{V_{DS}^2}{2}$), so gm is relatively linear with respect to V_{DS} . It is primarily determined by the overdrive voltage V_{OV} , the NMOS operates in the linear.

$$I_D = K_n (V_{ov} * V_{DS} - \frac{V_{DS}^2}{2}).$$

That's make the relation linear which with *the relation* $g_m = \frac{\partial I_D}{\partial V_{GS}}$ make gm relatively linear.

Saturation Region when ($V_{DS} > V_{ov}$):

As V_{DS} increases and becomes greater than V_{ov} , the NMOS enters the saturation region. In this region, gm starts to saturate with increasing V_{DS} . The reason for this saturation is the square law $I_D = \frac{K_n^2}{2} * V_{ov}^2 (1 + \gamma V_{DS})$ which with *the relation* $g_m = \frac{\partial I_D}{\partial V_{GS}}$ make gm relatively constant.

- In the first part of the curve, is the relation linear? Why?

Yes, because in this region the system is in triode and as we shown the triode region has linear relation between g_m and V_{DS} .

- Does g_m saturate? Why?

YES, as in saturation the square law $I_D = \frac{K_n}{2} * V_{ov}^2 (1 + \gamma V_{DS})$ is valid and $g_m = \frac{\partial I_D}{\partial V_{GS}}$

So g_m will be relatively constant and saturate.

- Where do you want to operate the transistor for analog amplifier applications? Why?

For analog amplifier applications we want to operate the transistor in the saturation region, as I_D depends only on V_{GS} (it is also has a little dependent on V_{DS} because of the channel length modulation) and g_m is high which mean high gain.

3) Comment on the variation of r_o vs V_{DS} .

- Does r_o saturate just after the transistor enters saturation similar to g_m ? Why?

NO, It saturates , but not similar to g_m it takes more time than g_m before saturation because the channel length modulation effect ,as r_o increase with channel length modulation because V_a depending on V_{DS} , and its effect appears because the channel pinch-off.

- Does r_o increase if the transistor is biased more into saturation?

YES, it will increase, because of the channel length modulation effect (Early effect).

- Should we operate the transistor at the edge of saturation?

NO, because it has small r_o , so its gain will be small and if the input is sinusoidal then half of the signal will be amplified in the triode region and the other half will be in the saturation region that make a distortion in the output.

- Where do you want to operate the transistor for analog amplifier applications? Why?

For analog amplifier applications we want to operate the transistor in the saturation region, as r_o is high which mean high gain. And also because of the other reasons we shown before